Supporting Information

Low Loss Photopatternable Matrix Materials for LWIR-Metamaterial Applications

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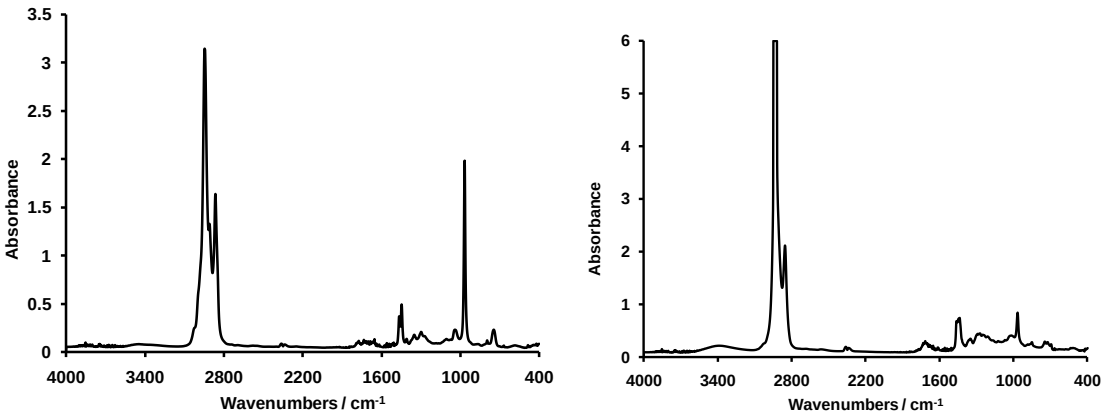

Figure S1. IR spectra for polynorbornene taken from free-standing films (20-25 μm) before (left) and after cross-linking (right).

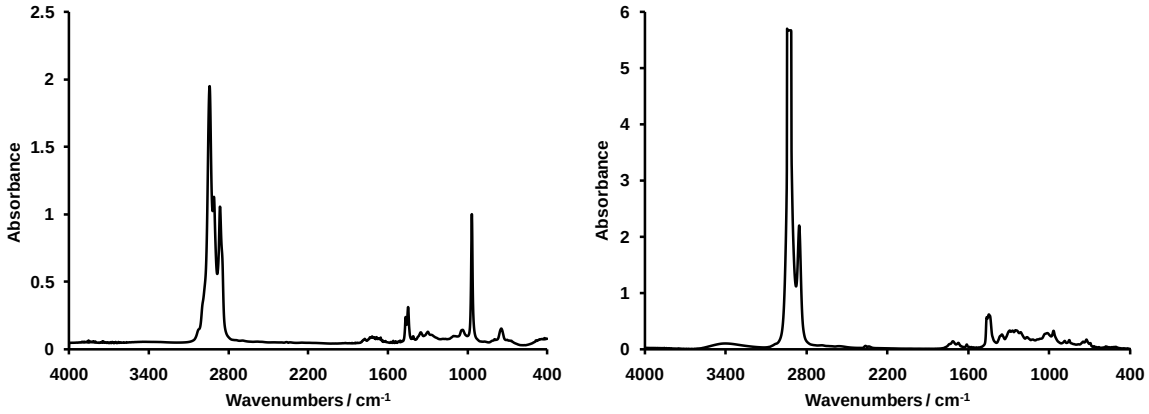

Figure S2. IR spectra for partially hydrogenated polynorbornene (18.2%) taken from free-standing films (20-25 µm) before (left) and after cross-linking (right).

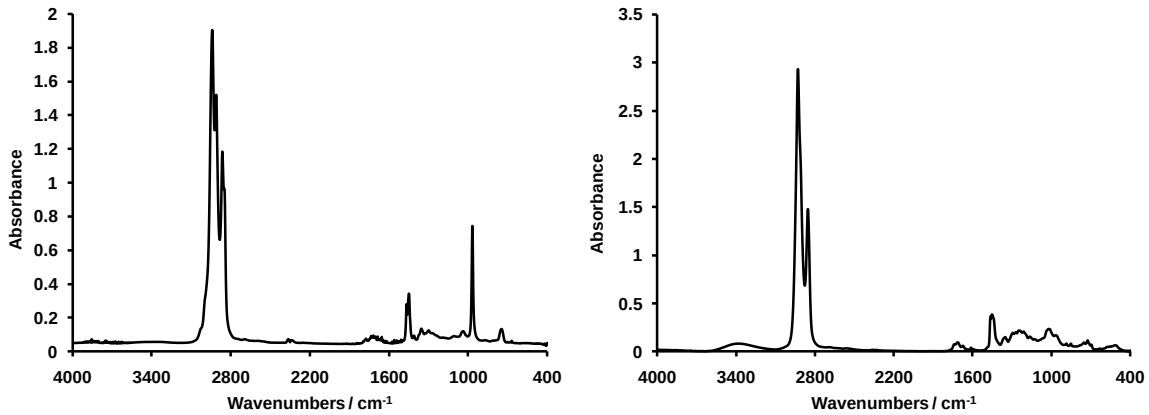

Figure S3. IR spectra for partially hydrogenated polynorbornene (41%) taken from free-standing films (20-25 µm) before (left) and after cross-linking (right).

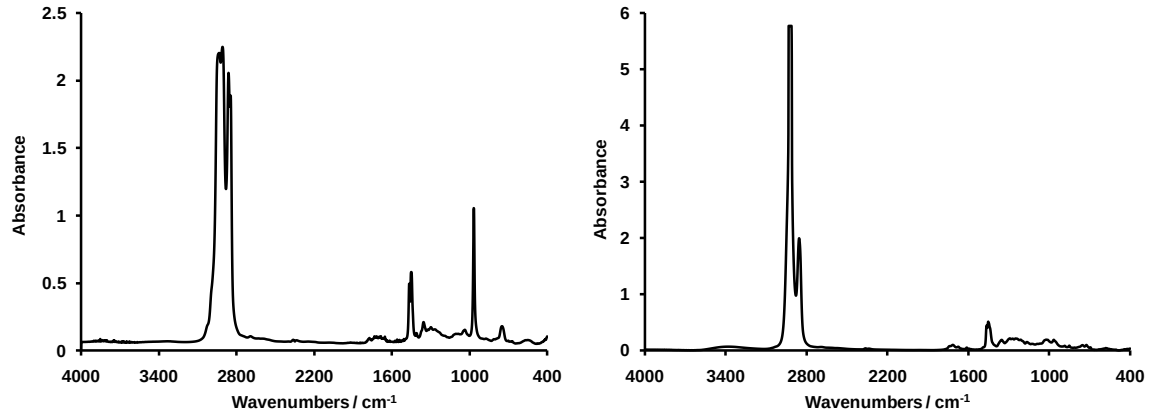

Figure S4. IR spectra for partially hydrogenated polynorbornene (55.9%) taken from free-standing films (20-25 µm) before (left) and after cross-linking (right).

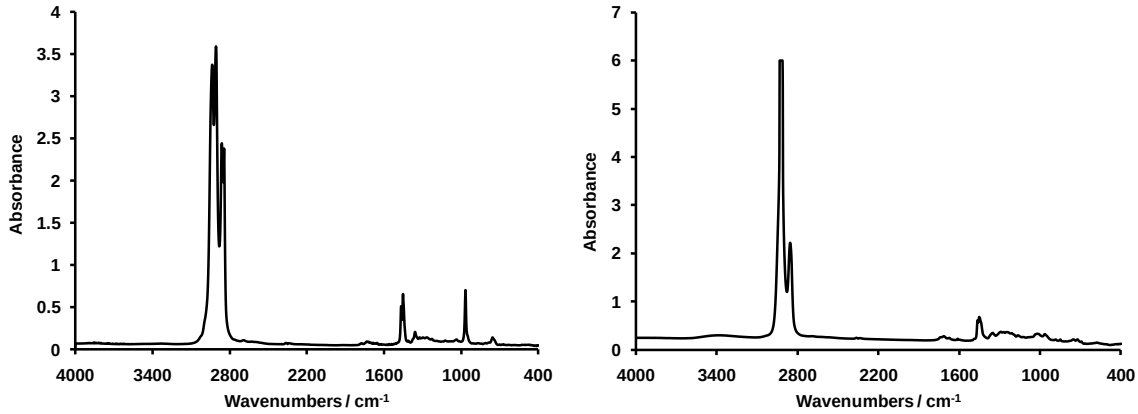

Figure S5. IR spectra for partially hydrogenated polynorbornene (72.4%) taken from free-standing films (20-25 μm) before (left) and after cross-linking (right).